

1 1. A method comprising:
2 aging a silica slurry for at least fifty days
3 from its manufacture date; and
4 using the aged slurry to chemical mechanical
5 polish a tantalum containing layer.

1 2. The method of claim 1 including using chemical
2 mechanical polishing with an aged slurry to form copper
3 metal lines.

1 3. The method of claim 1 including polishing through
2 a copper layer and a copper seed layer down to a tantalum
3 containing layer.

1 4. The method of claim 3 including polishing through
2 the tantalum containing layer down to a dielectric.

1 5. The method of claim 1 including using aged silica
2 slurries to reduce defects when polishing a tantalum
3 containing layer.

1 6. A method comprising:
2 receiving a silica slurry;
3 determining its age from its date of manufacture;
4 and

5 when its age is greater than fifty days, using
6 the slurry to chemical mechanical polish a tantalum
7 containing layer.

1 7. The method of claim 6 including using chemical
2 mechanical polishing with an aged slurry to form copper
3 metal lines.

1 8. The method of claim 6 including polishing through
2 a copper layer and a copper seed layer down to a tantalum
3 containing layer.

1 9. The method of claim 8 including polishing through
2 the tantalum containing layer down to a dielectric.

1 10. The method of claim 6 including using an aged
2 silica slurry to reduce defects when polishing tantalum
3 containing layers.

1 11. A method comprising:
2 aging a silica slurry for at least fifty days
3 from its data of manufacture; and
4 using the aged slurry to chemical mechanical
5 polish a metal layer.

1 12. The method of claim 11 including using the slurry
2 to polish a barrier layer.

1 13. The method of claim 12 including using the slurry
2 to polish a tantalum containing layer.

1 14. The method of claim 11 including using chemical
2 mechanical polishing with an aged slurry to form copper
3 metal lines.

1 15. The method of claim 11 including polishing
2 through a copper layer and a copper seed layer down to a
3 tantalum containing layer.

1 16. A method comprising:
2 aging a slurry for at least fifty days from its
3 date of manufacture; and
4 using the aged slurry to chemical mechanical
5 polish a layer.

1 17. The method of claim 16 including aging a silica
2 slurry.

1 18. The method of claim 16 including using the aged
2 slurry to chemical mechanical polish a metal layer.

1 19. The method of claim 16 including using the aged
2 slurry to chemical mechanical polish a non-metal layer.

1 20. The method of claim 16 including aging a slurry
2 selected from the group including silica, alumina, and
3 ceria.